FIG. 1

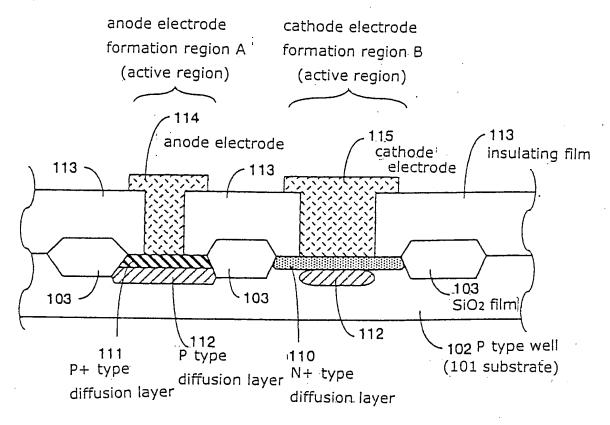
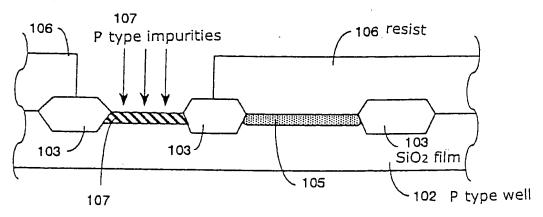


FIG. 2 (a) anode electrode cathode electrode formation region formation region 103 SiO2 film element isolation region 103 103 102 P type well (101 substrate)

FIG. 2 (b) 105 104 resist 104 N type impurities 103 103

FIG. 2 (c)

103



105

SiO2 film

102 P type well

FIG. 3 (a)

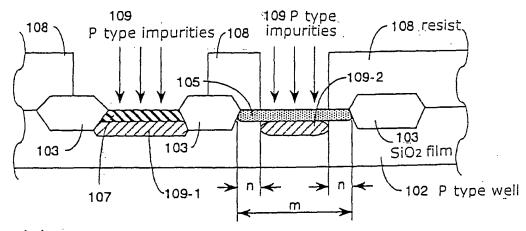
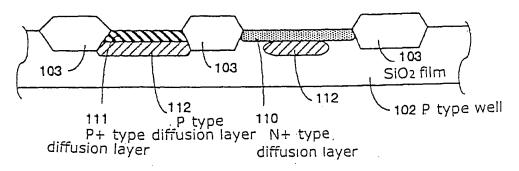
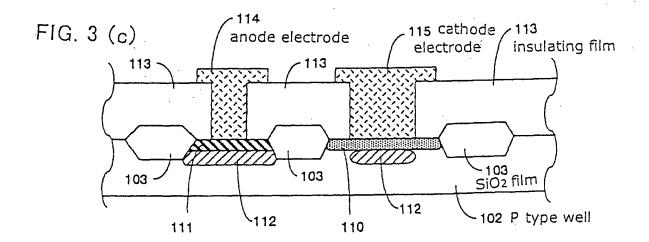
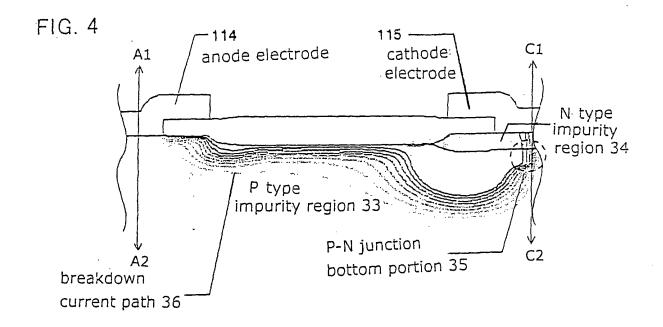
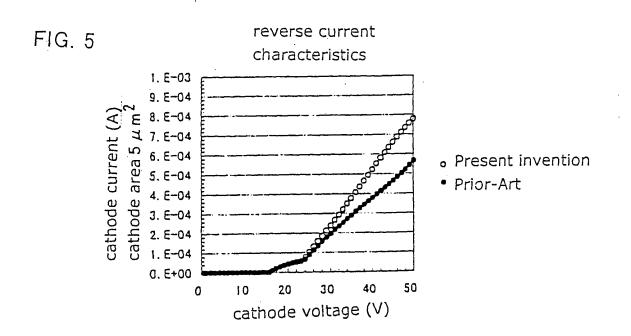


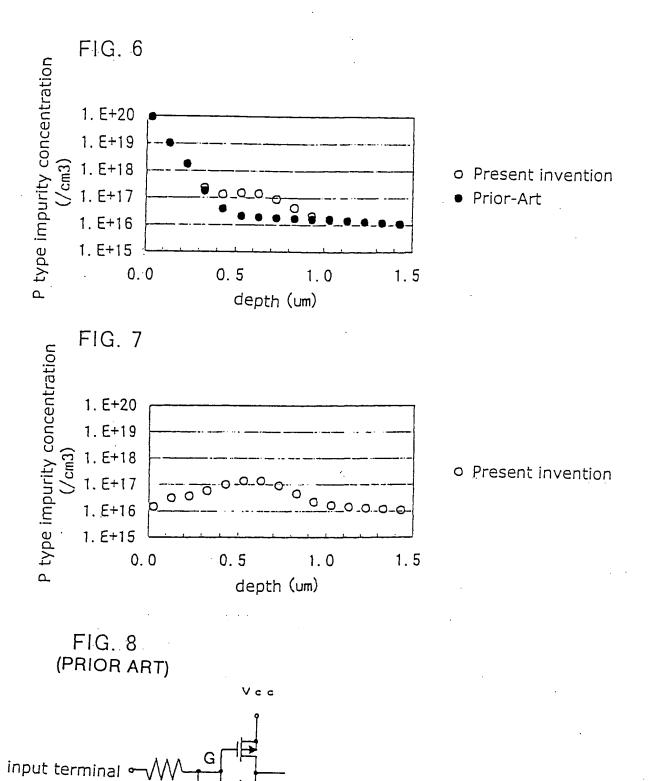
FIG. 3 (b)











GND

